

1763

PATENT
Attorney Docket No. 7363.0010

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Reissue Application of:

U.S. Patent No.: 5,792,261

Inventor: Kiichi HAMA et al.

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For: PLASMA PROCESS
APPARATUS



Group Art Unit: 1763

Examiner: Alejandro Mulero, L.

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

AMENDMENT

In response to the Office Action dated December 27, 2000, please amend this reissue application as follows:

IN THE CLAIMS:

1. (Amended) An apparatus for processing a process region of a substrate:
A' using a plasma, comprising:
a container substantially formed of a conductive material;
a partition plate dividing said container into an air-tight process chamber and an air-tight auxiliary chamber, and having a window plate made of dielectric;
a main exhaust pump [exhaust] for exhausting and setting said process chamber to a vacuum;

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